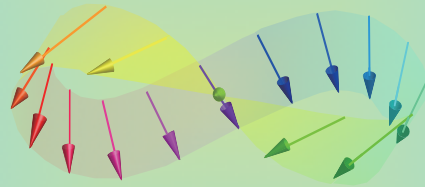


Semiconductor Devices

27



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11:00 Thursday, 4/December/2014 (P/T 005)



Exercise 6

Calculate the depletion layer capacity at a reverse bias $V_R = 0.5$ V in a Au/*n*-Si Schottky diode. Assume the following parameters:

Au work function: $\phi_M = 4.80$ eV

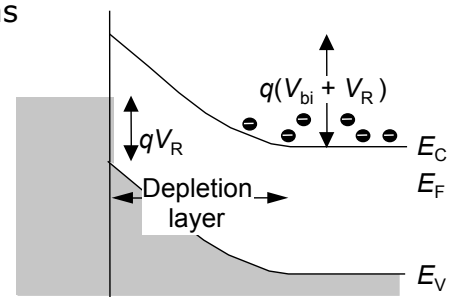
n-region: doping density of $N_D = 1 \times 10^{21}$ m⁻³

Si electron affinity: $\chi = 4.05$ eV

Si Fermi level: $E_F = E_C - 0.15$ eV

permittivity: $\epsilon = \epsilon_r \times \epsilon_0 = 12.0 \times 8.854 \times 10^{-12}$ F/m

and $q = 1.6 \times 10^{-19}$ C.





The built-in potential can be calculated as

$$qV_{bi} = \phi_B - (E_C - E_F)$$

For an n -type contact,

$$\phi_M < \chi : (\quad) \text{ contact}$$

$$\phi_M > \chi : (\quad) \text{ contact with the barrier height of } \phi_B = \phi_M - \chi$$

Hence,

$$qV_{bi} =$$

By substituting the given parameters,

$$qV_{bi} = (4.80 - 4.05) - 0.15 =$$

Depletion layer capacity C is

$$\begin{aligned} C &= \frac{\epsilon}{w} = \sqrt{\frac{q\epsilon N_D}{2(V_{bi} + V_R)}} \\ &= \sqrt{\frac{1.6 \times 10^{-19} \cdot 12.0 \times 8.854 \times 10^{-12} \cdot 1 \times 10^{21}}{2(0.60 + 0.5)}} \\ &= \sqrt{\frac{1.70 \times 10^{-8}}{1.3}} = 1.14 \dots \times 10^{-4} [\text{C}] \\ &\approx \end{aligned}$$

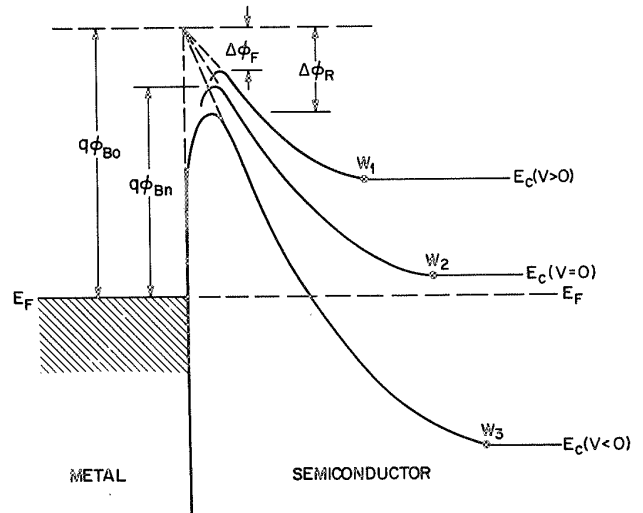
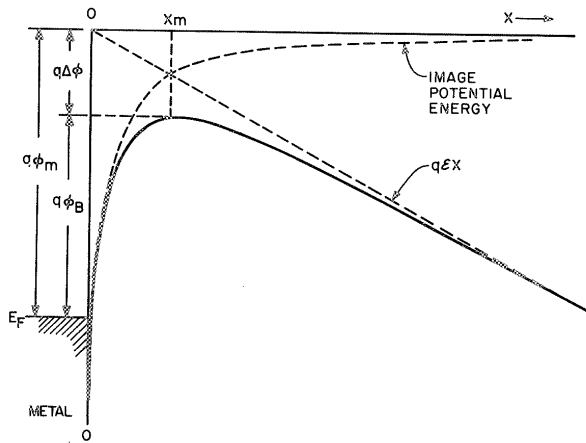
27 Metal Oxide Semiconductor Junction

- Bias application
- Surface space-charge
 - MOS FET



Realistic Schottky Barrier

Image force and Schottky barrier :

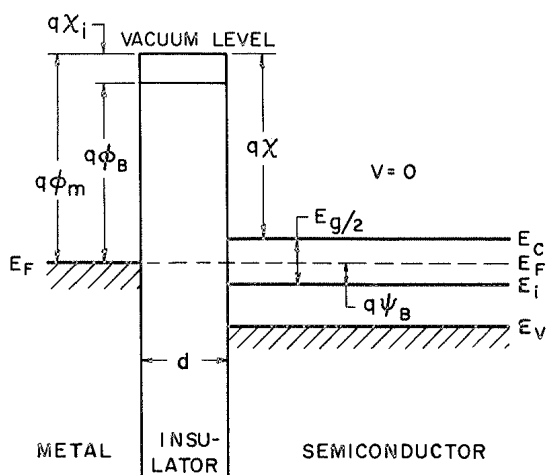


* S. M. Sze, *Physics of Semiconductor Devices* (Wiley, New York, 2006).

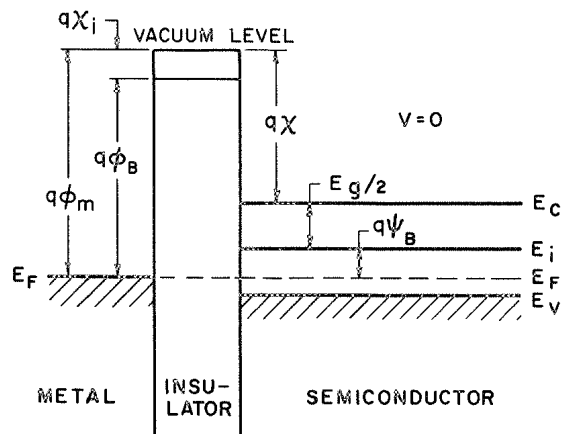


Metal Oxide Semiconductor Junction

n-type semiconductor at $V = 0$:



p-type semiconductor at $V = 0$:

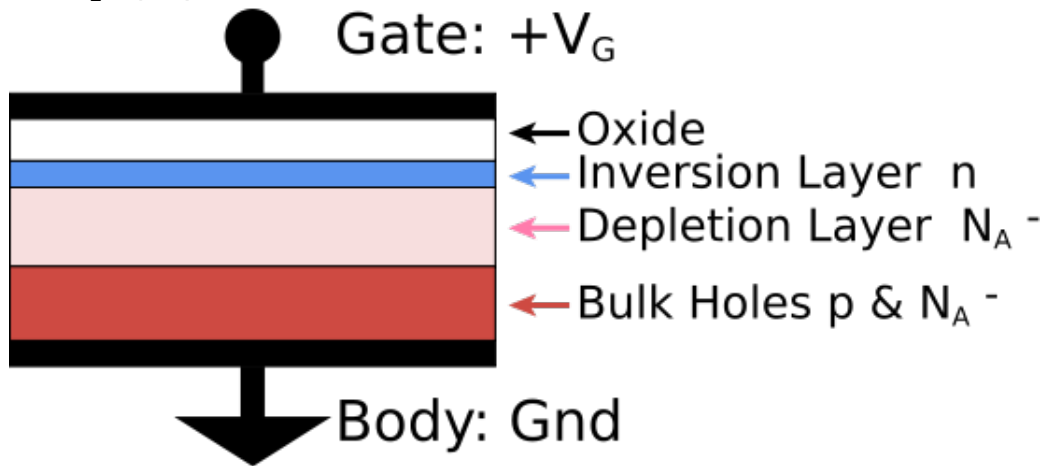


* S. M. Sze, *Physics of Semiconductor Devices* (Wiley, New York, 2006).



Metal Oxide Semiconductor (MOS)

p-type Si / SiO₂ / poly-Si :



In 2007, Intel introduced p-type Si / high-k oxides (HfO₂ etc.) / metal.

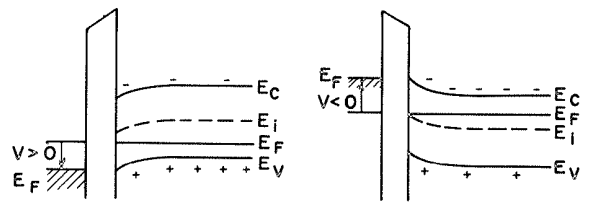
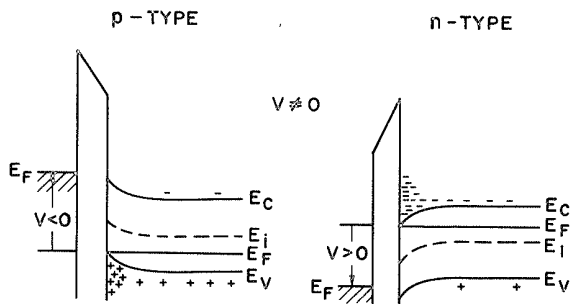
* <http://www.wikipedia.org/>



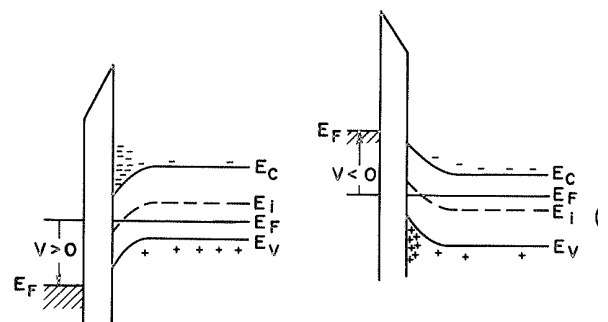
Bias Applications

Reverse bias () :

Forward bias () :



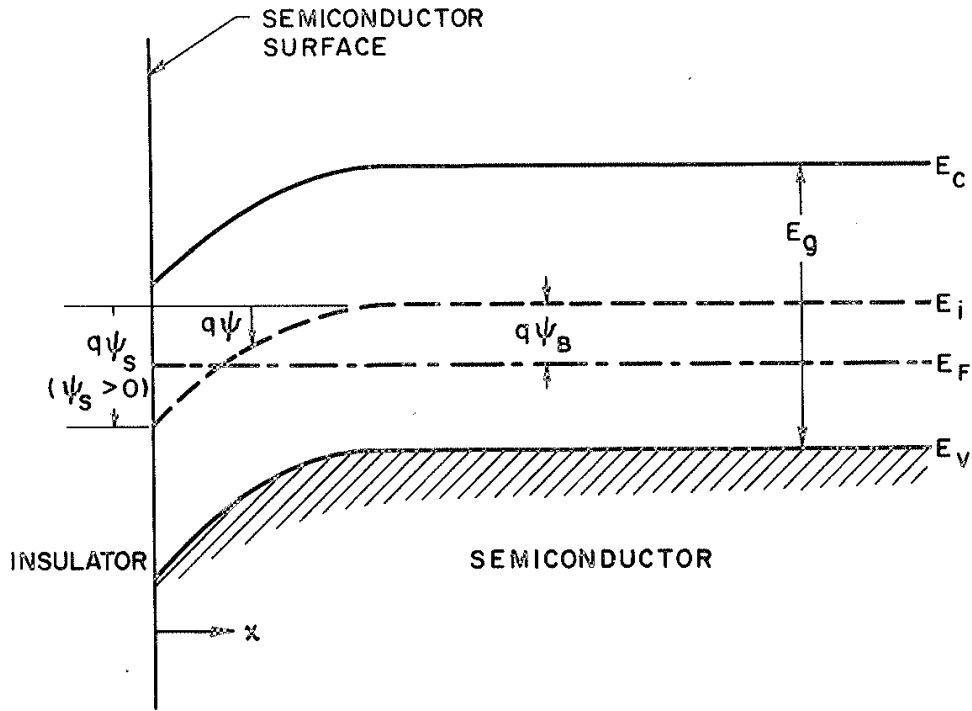
Forward bias () :





Surface Space-Charge

p-type semiconductor :

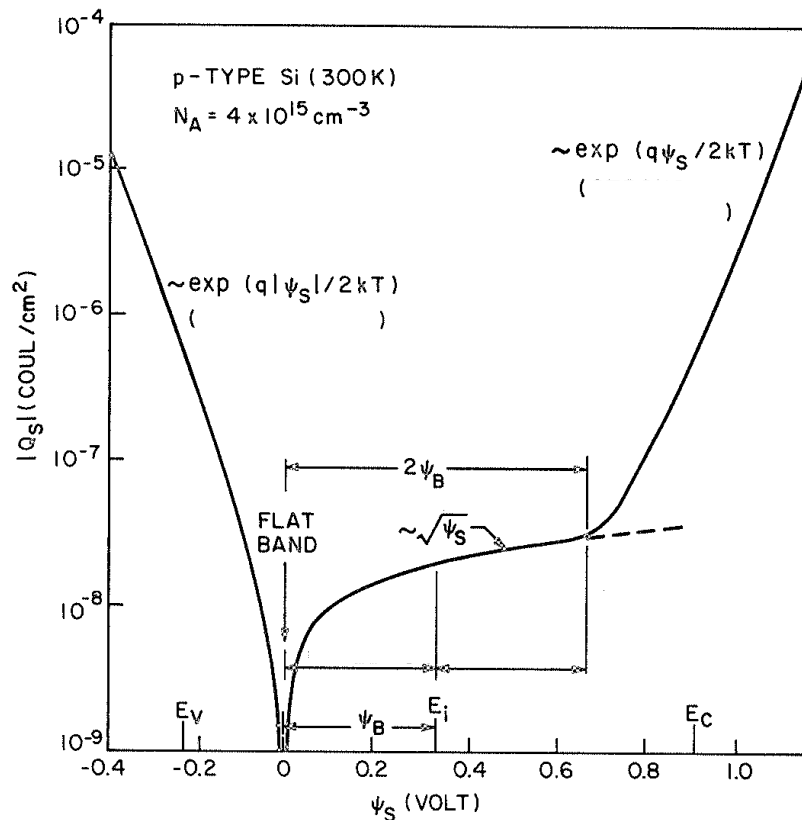


* S. M. Sze, *Physics of Semiconductor Devices* (Wiley, New York, 2006).



Space-Charge Variation

With different surface potentials ψ_s :

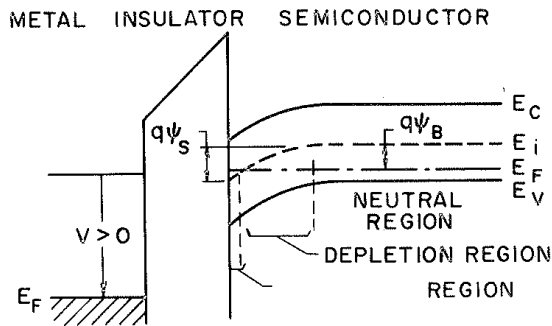


* S. M. Sze, *Physics of Semiconductor Devices* (Wiley, New York, 2006).

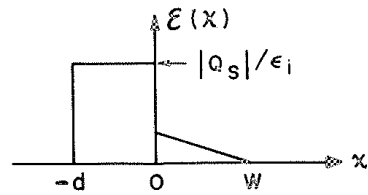


Charge Distributions

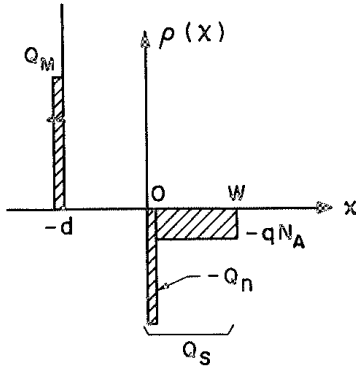
Band diagram of a metal oxide semiconductor junction under an inversion condition :



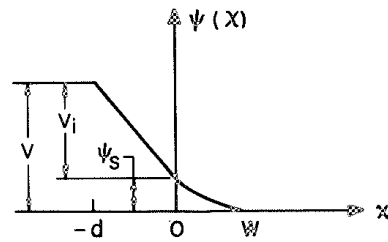
Electric field distributions :



Charge distributions :



Potential distributions :

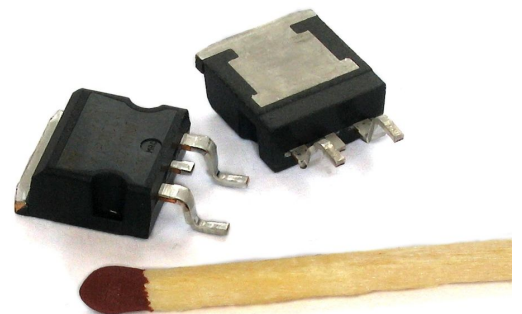
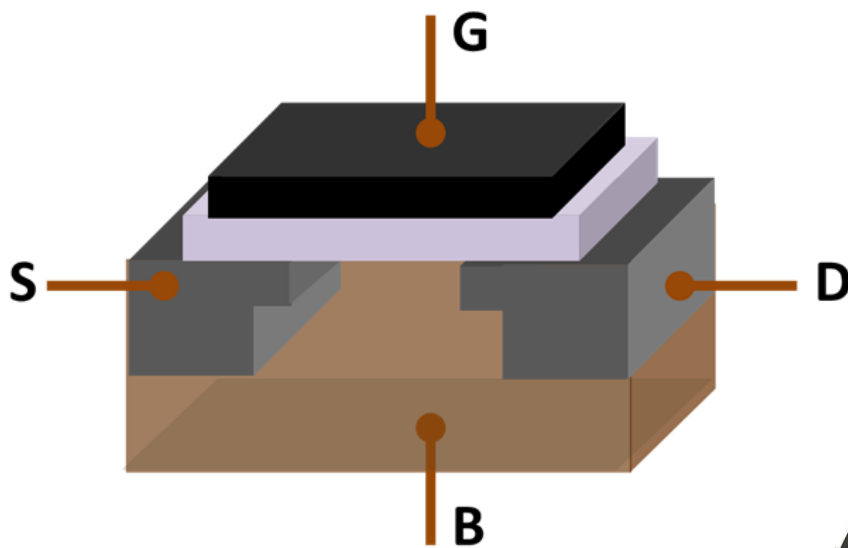


* S. M. Sze, *Physics of Semiconductor Devices* (Wiley, New York, 2006).



MOS Field Effect Transistor (FET)

One of the most popular transistors for amplification and switching :

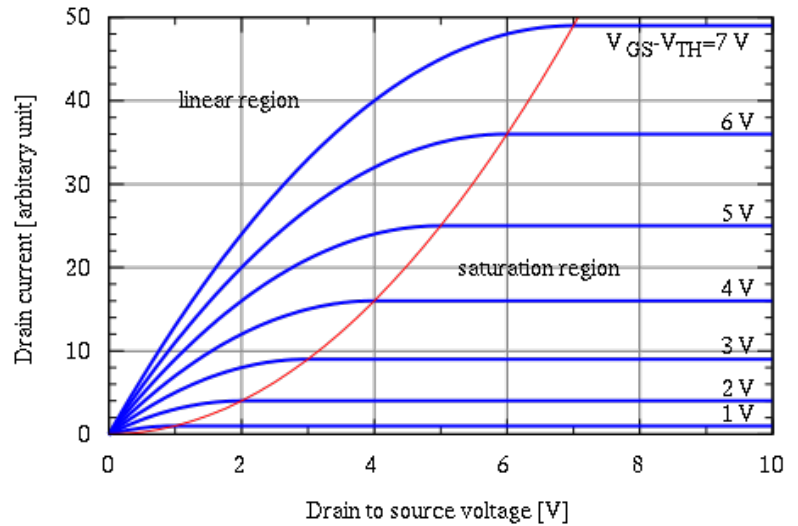
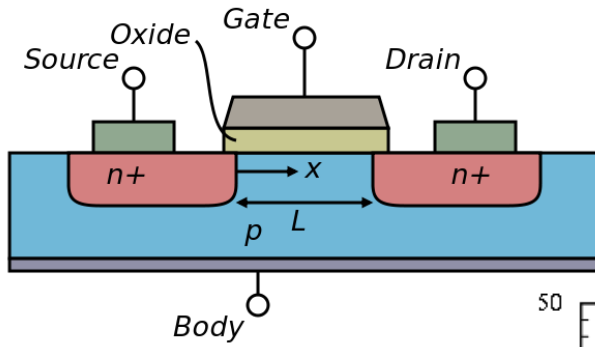


* <http://www.wikipedia.org/>



MOS FET Operation

Current-Voltage characteristics :



* <http://www.wikipedia.org/>



MOS FET Operation

Gate functionality :



* <https://www.youtube.com/watch?v=DquJSQasWG0>